Tool ID: 409 Tool Location: 117

Equipment Information Sheet

Heidelberg Mask Writer - DWL66FS

Manager:Garry Bordonaro607-254-4936Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

SAFETY

• System uses a class IIIb laser that is interlocked with chamber door to reduce the laser class to class I

USAGE RESTRICTIONS SCHEDULING/SIGN-UP RESTRICTIONS

- Maximum 4 hr block reservations anytime
- · Maximum 12 hours reserved in advance

Minimum Tool Time: 30 minutes

MATERIALS COMPATIBILITY CATEGORY

Tool Category 5: Class A and B Metals and Compounds **Not Allowed** Allowed Tool category 1/1E, 2, 3, and 4 materials Silicon Based Substrates and Films III/V compound Semiconductors Glass Substrates PECVD and ALD Films Cured organics and baked Photoresist CNF Class A, B, and Refractory metals Exposed Gold, Silver, Copper Alkali and Alkaline Compounds Organic/Biology Molecules prepared-w/salt buffers High Vapor Pressure Materials (Mg, Ca, Zn)* Some tool restrictions on high vapor pressure materials may apply Soft organic materials

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

Additional Material Restrictions and Exceptions

- Masks Only either 0.090" or 0.250" thick
- NO wafers, pieces or other substrates without Staff assistance

Last Updated: 12/04/2020